

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

Form PTO-1449 (Modified)
(Use several sheets if necessary)

Sheet 1 of 3 Attorney Docket No. 54008.8100.US01 (P01-0015US2)

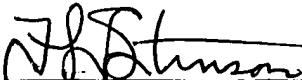
COMPLETE IF KNOWN

Application Number	Not Yet Assigned
Confirmation Number	
Filing Date	November 25, 2003
First Named Inventor	Eric J. BERGMAN
Group Art Unit	
Examiner Name	

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	U.S. Patent or Application		Name of Patentee or Inventor of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		NUMBER	Kind Code (if known)			
thb	AA	4,186,032		Ham	01/29/80	
	AB	4,749,440		Blackwood et al.	06/07/88	
	AC	4,817,652		Liu	04/04/89	
	AD	4,917,123		McConnell et al.	04/17/90	
	AE	4,974,530		Lyon	12/04/90	
	AF	5,032,218		Dobson	07/16/91	
	AG	5,055,138		Slinn	10/08/91	
	AH	5,063,609		Lorimer	11/05/91	
	AI	5,071,485		Matthews et al.	12/10/91	
	AJ	5,105,556		Kurokawa et al.	04/21/92	
	AK	5,120,370		Mori et al.	06/09/92	
	AL	5,160,378		Tuunanen	11/03/92	
	AM	5,181,985		Lampert et al.	01/26/93	
	AN	5,232,511		Bergman	08/03/93	
	AO	5,232,870		Ito et al.	08/03/93	
	AP	5,234,540		Grant et al.	08/10/93	
	AQ	5,235,995		Bergman et al.	08/17/93	
	AR	5,244,000		Stanford et al.	09/14/93	
	AS	5,246,526		Yamaguchi et al.	09/21/93	
	AT	5,248,380		Tanaka	09/28/93	
	AU	5,308,745		Schwartzkopf	05/03/94	
	AV	5,326,406		Kaneko et al.	07/05/94	
	AW	5,366,757		Lin	11/22/94	
	AX	5,372,651		Kodama	12/13/94	
	AY	5,378,317		Kashiwase et al.	01/03/95	
	AZ	5,415,191		Mashimo et al.	05/16/95	
	BA	5,447,640		Orni	09/05/95	
	BB	5,464,480		Matthews	11/07/95	
	BC	5,503,708		Koizumi et al.	04/02/96	
	BD	5,520,744		Fujikawa et al.	05/28/96	
	BE	5,571,367		Nakajima et al.	11/05/96	
	BF	5,626,769		Sawamoto	05/06/97	
	BG	5,632,847		Ohno et al.	05/27/97	
	BH	5,647,386		Kaiser	07/15/97	
	BI	5,658,615		Hasebe et al.	08/19/97	
	BJ	5,705,089		Sugihara et al.	01/06/98	
	BK	5,706,842		Caimi et al.	01/13/98	
thb	BL	5,714,203		Schellenberger et al.	02/03/98	

EXAMINER



DATE CONSIDERED

12/10/05

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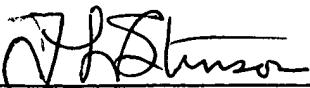
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Examiner Initials*	Cite No.	U.S. Patent or Application		Name of Patentee or Inventor of Cited Document	Date of Publication or Filing Date of Cited Document
		NUMBER	Kind Code (if known)		
NHS	BM	5,730,806		Caimi et al.	03/24/98
	BN	5,749,975		Li et al.	05/12/98
	BO	5,762,755		McNeilly et al.	06/09/98
	BP	5,776,296		Matthews	07/07/98
	BQ	5,803,982		Kosofsky et al.	09/08/98
	BR	5,810,940		Fukazawa	09/22/98
	BS	5,832,177		Shingawa	11/03/98
	BT	5,845,662		Summitsch	12/08/98
	BU	5,858,107		Chao et al.	01/12/99
	BV	5,896,875		Yoneda	04/27/99
	BW	5,911,837		Matthews	06/15/99
	BX	5,916,366		Ueyama et al.	06/29/99
	BY	5,944,907		Ohmi	08/31/99
	BZ	5,950,643		Miyazaki et al.	09/14/99
	CA	5,964,952		Kunze-Concewitz	10/12/99
	CB	5,964,954		Matsukawa et al.	10/12/99
	CC	5,971,368		Nelson et al.	10/26/99
	CD	6,030,932		Leon et al.	02/29/00
	CE	6,146,469		Toshima	11/14/00
	CF	6,249,933		Berfield	06/26/01
	CG	6,267,125		Bergman et al.	07/31/01
	CH	6,273,108		Bergman et al.	08/14/01
NHS	CI	6,299,696		Kamikawa et al.	10/09/01

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent or Application		Name of Patentee or Applicant of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Office	NUMBER				
NHS	CJ	JP	52-012063	Hiroshi Ikeda	04/04/1977		X
	CK	JP	S61-004232	Yukinobu Tanno et al.	01/10/1986		X
	CL	JP	62-117330	Sanyo Elec. Co., Ltd.	05/28/1987		
	CM	JP	63-110732	NEC Corp.	05/16/1988		
	CN	JP	64-042129	Hitachi Ltd.	02/14/1989		
	CO	EP	0 344 764	Wacker Chemitronic	12/06/1989		
	CP	JP	H01-262627	Nippon Denki, K.K.	10/19/1989		X
	CQ	JP	03-072626	Dainippon Screen Mfg. Co., Ltd.	03/27/1991		X
	CR	JP	H03-208900	Nippon Steel Corp.	09/12/1991		X
NHS	CS	JP	H04-125927	Fujitsu, Ltd.	04/27/1992		X

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First Named Inventor Eric J. BERGMAN

Group Art Unit

Examiner Name

Sheet

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of

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Attorney Docket No. 54008.8100.US01 (P01-0015US2)

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		NUMBER	Kind Code (if known)			
CT	JP	HO4-298038		Hitachi Cable, Ltd.	10/21/1992	
CU	JP	04-302144		Hitachi, Ltd.	10/26/1992	
CV	JP	04-302145		Hitachi Ltd.	10/26/1992	
CW	JP	04-370931		Hitachi Zosen Corp.	12/24/1992	X
CX	JP	05-013398		Hitachi Zosen Corp.	01/22/1993	X
CY	JP	05-109686		Nippon Steel Corp.	04/30/1993	
CZ	EP	0 548 596 A2		Chlorine Eng. Corp. Ltd.	06/30/1993	X
DA	JP	05-259139		Hitachi Ltd.	10/08/1993	
DB	JP	05-283389		NEC Corp.	10/29/1993	X
DC	JP	06-204130		Mitsubishi Electric Corp.	07/22/1994	X
DD	JP	07-159980		Nikon Corp.	06/23/1995	
DE	JP	08-008222		Sony Corporation	01/12/1996	
DF	EP	0 702 399		Siemens AG	03/20/1996	
DG	JP	08-160032		Toshiba Corp.	06/21/1996	
DH	EP	0 782 177 A2		Texas Instruments Incorporated	07/02/1997	X
DI	WO	99/S2654		Bergman et al.	10/21/1999	X
DJ	JP	52-100473		Yamanouchi Pharm.	08/23/1977	
DK	JP	64-008630		Tokyo Electron Ltd.	01/12/1989	
DL	JP	63-016127		Yamaha Motor Co. Ltd.	01/23/1988	
DM	JP	03-041729		Tokyo Electron Ltd.	02/22/1991	
DN	JP	01-192712		Nippon Mining Co. Ltd.	08/02/1989	

OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume issue number(s), publisher, city and/or country where published.	T

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(54008.8100.US01/LA033290.002)

 INFORMATION DISCLOSURE STATEMENT BY APPLICANT Form SB/08A (Use several sheets if necessary)				COMPLETE IF KNOWN	
				Application Number	10/721,495
				Confirmation Number	
				Filing Date	November 25, 2003
				First Named Inventor	Michael Kenny
				Group Art Unit	
				Examiner Name	
1	of	1		Attorney Docket No.	54008.8100.US01 (P01-0015US2)

U.S. PATENT DOCUMENTS

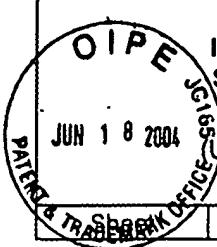
FOREIGN PATENT DOCUMENTS

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COMPLETE IF KNOWN

Application Number	10/721,495
Confirmation Number	
Filing Date	November 25, 2003
First Named Inventor	Michael KENNY
Group Art Unit	
Examiner Name	
Attorney Docket No.	54008.8100.US01 (P01-0015US2)

U.S. PATENT DOCUMENTS

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		NUMBER	Kind Code (if known)			
JKS	DO	6,551,409		DeGendt	04/22/03	
JKS	DP	2002/0011257		DeGendt	01/31/02	

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Examiner Initials*	Cite No.	Foreign Patent or Application			Name of Patentee or Applicant of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Office	NUMBER	Kind Code (if known)				

OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS

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JKS	DQ	Alder, M., et al., "The Kinetics and Mechanism of Hydroxide Ion Catalyzed Ozone Decomposition in Aqueous Solution." <i>J. Am. Chem. Soc.</i> , 72:1884-1886 (1950).	
	DR	Amick, J.A., "Cleanliness and the Cleaning of Silicon Wafers." <i>Solid State Technology</i> , pp. 47-52 (Nov. 1976).	
	DS	Anantharaman, et al., "ORGANICS: Detection and Characterization of Organics in Semiconductor DI Water Processes." <i>Ultrapure Water</i> , pp. 30-36 (Apr. 1994).	
	DT	Baumgärtner, H., et al., "Ozone Cleaning of the Si-SiO ₂ System." <i>Appl. Phys. A</i> , 43:223-226 (1987).	
	DU	Bedge, S., et al., "Kinetics of UV/O ₂ Cleaning and Surface Passivation: Experiments and Modeling." <i>Mat. Res. Soc. Symp. Proc.</i> , 259:207-212 (1992).	
	DV	Bolon, D.A., et al., "Ultraviolet Depolymerization of Photoresist Polymers," <i>Polymer Engineering and Science</i> , 12(2):108-111 (March 1972)	
JKS	DW	Christenson, K., et al., "Deionized Water Helps Remove Wafer Stripping 'Resist'-ance." www.precisioncleaningweb.com--Precision Cleaning Web--Archives , pp. 10-20 (Apr. 1998).	

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				Application Number	10/721,495
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				Filing Date	November 25, 2003
				First Named Inventor	Michael KENNY
				Group Art Unit	
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Sheet	2	of	4	Attorney Docket No.	54008.8100.US01 (P01-0015US2)

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Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume/issue number(s), publisher, city and/or country where published.				T
<i>JRS</i>	DX	Egitto, F.D., et al., "Removal of Poly (Dimethylsiloxane) Contamination From Silicon Surfaces With UV/Ozone Treatment." <i>Mat. Res. Soc. Symp. Proc.</i> , 385:245-250 (1995).				
	DY	Gabriel, C., et al., "Reduced Device Damage Using An Ozone Based Photoresist Removal Process." <i>SPIE Advances in Resist Technology and Processing VI</i> , 1086:598-604 (1989).				
	DZ	Ganesan, G., et al., "Characterizing Organic Contamination in IC Package Assembly." <i>The Int'l. Soc. for Hybrid Microelectronics</i> , 17(2), Second Quarter, 152-160 (1994).				
	EA	Golland, D.E., et al., "The Clean Module: Advanced Technology for Processing Silicon Wafers." <i>Semiconductor Int'l.</i> , pp. 154-157 (Sep. 1987).				
	EB	Goulding, M.R., "The selective epitaxial growth of silicon," <i>Materials Science and Engineering</i> , Vol. B17, pp. 47-67 (1993).				
	EC	Heyns, M.M., et al., "New Wet Cleaning Strategies for Obtaining Highly Reliable Thin Oxides." <i>MRP Symposium Proceedings on Materials Research Society</i> , Spring Meeting, San Francisco, CA, Apr. 12-13, p. 35 (1993).				
	ED	Huynh, C., et al., "Plasma versus ozone photoresist ashing: Temperature effects on process-induced mobile ion contamination." <i>J. Vac. Sci. Technol.</i> , B9(2):353-356 (Mar./Apr. 1991).				
	EE	Isagawa, T., et al., "Ultra Clean Surface Preparation Using Ozonized Ultrapure Water." <i>Extended Abstracts of the 1992 Int'l. Conf. on Solid State Devices and Materials</i> , pp. 193-195 (1992).				
	EF	Kasi, S., et al., "Surface Hydrocarbon Removal from Si by UV/Ozone." <i>ECS Extended Abstracts</i> , No. 458, pp. 691-692 (1990).				
	EG	Kasi, S., et al., "Vapor phase hydrocarbon removal for Si processing." <i>Appl. Phys. Lett.</i> , 57(20):2095-2097 (Nov. 1990).				
<i>JRS</i>	EH	Kern, W., "The Evolution of Silicon Wafer Cleaning Technology." <i>J. Electrochem. Soc.</i> , 137(6):1887-1892 (Jun. 1990).				

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				Application Number	10/721,495
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				Filing Date	November 25, 2003
				First Named Inventor	Michael KENNY
				Group Art Unit	
				Examiner Name	
Sheet	3	of	4	Attorney Docket No.	54008.8100.US01 (P01-0015US2)

OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS					
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<i>JPS</i>	EI	Krusell, W.C., et al., "Cleaning Technologies for High Volume Production of Silicon Wafers." <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology in Semiconductor Device Mfg.</i> , pp. 23-32 (Oct. 1989).			
	EJ	Krusell, W.C., et al., "The Characterization of Silicon Substrate Cleaning Treatments by use of SIMS and MOS Electrical Testing." <i>ECS Extended Abstracts</i> , No. 229, p. 331-332 (1986).			
	EK	Nelson, S., "Ozonated water for photoresist removal." <i>Solid State Technology</i> , p. 107-112 (Jul. 1999).			
	EL	Ohmi, T., et al., "Native Oxide Growth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water." <i>J. Electrochem. Soc.</i> , 140(3):804-810 (Mar. 1993).			
	EM	Sehested, K., et al., "Decomposition of Ozone in Aqueous Acetic Acid Solutions (pH 0-4)." <i>J. Phys. Chem.</i> , pp. 1005-1009 (1992).			
	EN	Shimada, H., et al., "Residual-Surfactant-Free Photoresist Development Process." <i>J. Electrochem. Soc.</i> , 139(6):1721-1730 (Jun. 1992).			
	EO	Suemitsu, M., et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (I)-Optimization of the HF Treatment." <i>Japanese Journal of Applied Physics</i> , 28(12):2421-2424 (Dec. 1989).			
	EP	Tabe, M., "UV ozone cleaning of silicon substrates in silicon molecular beam epitaxy." <i>Appl. Phys. Lett.</i> , 45(10):1073-1075 (Nov. 1984).			
	EQ	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>ECS Extended Abstracts</i> , Phoenix, AZ, Abstract No. 506, pp. 753 (Oct. 13-17, 1991).			
	ER	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>Proc. of 2.sup.nd Int'l. Symposium on Cleaning Tech. In Semiconductor Device Mfg.</i> , pp. 18-25 (Oct. 1992).			
	ES	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Elec. Tech. and Devices Lab.</i> , pp. 1-26.			
<i>JPS</i>	ET	Vig, J., "UV/Ozone Cleaning of Surfaces: A Review." <i>Surface Contamination: Genesis, Detection, and Control</i> , pp. 235-253 (1979).			

EXAMINER <i>J. H. Johnson</i>	DATE CONSIDERED <i>12/10/05</i>
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				Filing Date	November 25, 2003
				First Named Inventor	Michael KENNY
				Group Art Unit	
				Examiner Name	
Sheet	4	of	4	Attorney Docket No.	54008.8100.US01 (P01-0015US2)

OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS						
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<i>JDS</i>	EU	Vig, J., et al., "UV/Ozone Cleaning of Surfaces." <i>IEEE Transactions on Parts, Hybrids, and Packaging</i> , Vol. PHP-12(4):365-370 (Dec. 1976).				
	EV	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Electronics Technology and Devices Laboratory</i> , ERADCOM, Ft. Monmouth, NJ, 07703-5302, pp. 1027-1034 (Sep./Oct. 1984).				
	EW	Zafonte, L., et al., "UV/Ozone Cleaning For Organics Removal on Silicon Wafers." <i>SPIE Optical Microlithography III: Technology for the Next Decade</i> , 470:164-175 (1984).				
	EX	Zazzera, L.A., et al., "XPS and SIMS Study of Anhydrous HF and UV/Ozone-Modified Silicon (100) Surfaces." <i>J. Electrochem. Soc.</i> , 136(2):484-491 (Feb. 1989).				
	EY	"Ozone Concentration Measurement in a Process Gas." <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (Dec. 1993).				
<i>JDS</i>	EZ	"Ozone for Semiconductor Applications." <i>Sorbios</i> , pp. 1-6 (Oct. 1991).				

EXAMINER <i>John Stinson</i>	DATE CONSIDERED <i>12/10/05</i>
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[54008.8100.US01/LA041610.019]	

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Form SB/08A
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O P E
I A P T
SEP 22 2005
P A T E N T & T R A D E M A R K S

COMPLETE IF KNOWN

Application Number	10/721,485
Confirmation Number	6048
Filing Date	November 25, 2003
First Named Inventor	Michael Kenny
Group Art Unit	1746
Examiner Name	Frankie L. Stinson
Attorney Docket No.	54008.8100.US01 (P05-0015US2)

Sheet 1 of 4

U.S. PATENT DOCUMENTS

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		Number-Kind Code ² (if known)			
FB	4,064,885		12-1977	Dussault et al.	
FC	4,633,804		01-1987	Arii	
FD	4,695,327		09-1987	Grebinski	
FE	4,778,532		10-1988	McConnell et al.	
FF	4,899,767		02-1990	McConnell et al.	
FG	5,039,349		08-1991	Schoeppel	
FH	5,147,499		09-1992	Szwejkowski et al.	
FI	5,423,944		03-1994	Wong	
FJ	5,518,542		05-1996	Matsukawa et al.	
FK	5,868,866		02-1999	Maekawa et al.	
FL	5,911,836		06-1999	Hada et al.	
FM	5,922,624		07-1999	Verhaverbeke et al.	
FN	5,927,306		Jul-99	Izumi et al.	
FO	5,975,098		11-1999	Yohaitani et al.	
FP	5,990,060		11-1999	Ohmi et al.	
FQ	6,003,527		12-1999	Netsu et al.	
FR	6,085,764		07-2000	Kobayashi	
FS	6,199,567		03-2001	Kanno et al.	
FT	6,202,658		03-2001	Fishkin et al.	
FU	6,235,112		05-2001	Satoh	
FV	6,240,933		06-2001	Bergman	
FW	6,295,999		10-2001	Bran	
FX	6,325,081		12-2001	Miki et al.	
FY	6,406,551		06-2002	Nelson et al.	
FZ	6,423,146		07-2002	Fukazawa	
GA	6,431,184		08-2002	Taniyama	

J. H. Stinson
12/10/05

INFORMATION DISCLOSURE STATEMENT BY APPLICANT Form SB/08A (Use several sheets if necessary)				COMPLETE IF KNOWN	
Sheet	2	of	4	Application Number	10/721,495
				Confirmation Number	6048
				Filing Date	November 25, 2003
				First Named Inventor	Michael Kenny
				Group Art Unit	1746
				Examiner Name	Frankie L. Stinson
				Attorney Docket No.	54008.8100.US01 (P05-0015US2)

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Inventor of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
PLS	GB	6,455,717	09-2002	Vaartstra	
	GC	6,497,768	12-2002	Bergman	
	GD	6,543,080	04-2003	Tomita et al.	
	GE	6,582,525	06-2003	Bergman	
	GF	6,626,189 B2	11-25-2002 F	Kashkoush et al.	
	GG	6,743,301	12-22-2000 F	Matsuno et al.	
	GH	6,817,370	11-2004	Bergman et al.	
	GI	6,843,857	01-2005	Bergman	
	GJ	6,869,487	03-2005	Bergman	
PLS	GK	2002/0066464 A1	06-2002	Bergman	
PLS	GL	2004/0154641 A1	08-12-2004	Montierth	


 12/10/05

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
Form SB/08A
(Use several sheets if necessary)

COMPLETE IF KNOWN

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FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Country Code	Number-Kind Code (if known)				
JKS	GM	DE	19801360 A1	7/22/1999	SEZ Semiconductor-Equipment Zubehor		
	GN	EP	0 587 889	03-23-1994	Ohmi, Tadahiro		
	GO	EP	0 890 658	01-1999			
	GP	GB	2 287 827	09-27-1995	NEC Corporation		
	GQ	JP	01-189921	07-31-1989	Mitsubishi Electric Corp.		
	GR	JP	04-079221	03-12-1992	Seiko Epson Corp.		
	GS	JP	04-164324	06-10-1992	NEC CORP.		
	GT	JP	05-136045	06-1993			
	GU	JP	07-155714	06-1995			
	GV	JP	08-288271	11-1996			
	GW	JP	08-064566	03-08-1996	Ryoden Semiconductor		
	GX	JP	09-139345	05-1997			
	GY	JP	10-144640	05-1998			
	GZ	JP	11-054427	02-1999			
	HA	JP	59-068930	04-1984			
	HB	JP	61-004232	01-10-1986	NEC Corp.		
JKS	HC	JP	2000-138188	05-2000			
JKS	HD	WO	WO01/07177 A1	02-01-2001	Semitool, Inc.		

Frankie L. Stinson
12/10/05

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
Form SB/08B
(Use several sheets if necessary)

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Attorney Docket No.	54008.8100.US01 (P05-0015US2)

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OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume/issue number(s), publisher, city and/or country where published.	T
JKS	HE	Bergman, E. et al., "HF-Ozone Cleaning Chemistry," Solid State Technology 46(7):115-124(2001)	

Frankie L. Stinson 12/10/05